Catalyst-free Growth of ZnOnanoleaves on ZnOseed layer/glassby Thermal Evaporation Method: Effects of Carrier Gas Flow Rate

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Here, we report for the first time the catalyst-free growth of ZnOnanoleaf on a glass substrate via thermal evaporation method. These nanoleaveswere grown on (75 \pm 5 nm) ZnOseed layers, which were deposited on glass substrates by radio frequency (RF) magnetron sputtering. Prior to synthesized ZnOnanoleaves, the sputtered ZnOseeds were annealed using the continuous wave (CW) CO₂ laser at 450 °C in air for 15 min. The effects of carrier gas flow rate on the morphological, structural, and optical properties were systematically studied using field emission scanning electron microscopy, X-ray diffraction and UV-Vis spectroscopy. The objective of the present study was achieved by obtaining ZnOnanoleaves and obtains the optimized parameters for the control of different morphologies of these nanoleaves.

Keywords: ZnO, nanoleaf, X-ray diffraction and UV-Vis spectroscopy.